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SPRING COLLEGE ON AMORPHOUS SOLIDS
AND THE LIQUID STATE

14 April - 18 June 1982

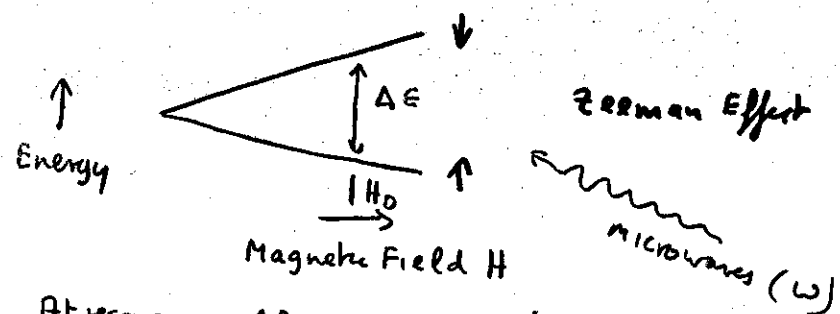
LUMINESCENCE AND SPIN RESONANCE IN AMORPHOUS SILICON

(Lecture II)

R.A. STREET
Xerox Corporation
Palo Alto Research Center
3333 Coyote Hill Road
Palo Alto, California 94304
USA

These are preliminary lecture notes, intended only for distribution to participants.
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Electron Spin Resonance ESR



At resonance $\Delta E = \text{const. } H_0 = \hbar \omega$

(Precession frequency $\gamma H_0 = \omega$)

For defects in semiconductors

$$H = M_B H_0 \cdot \underset{\substack{\uparrow \\ \text{spin}}}{g} \cdot \underset{\substack{\uparrow \\ \text{g-tensor}}}{S} + \underbrace{\sum_i I_i \cdot A_i \cdot S}_{\text{Hyperfine.}} \quad \text{nuclear moments}$$

Free electron $g = g_0 = 2.0023$

in solid $g = g_0 + \Delta g_{ij}$

$$\Delta g \sim \sum \frac{\langle d | V_{so}^i | \phi \rangle \langle \phi | L_{ij} | d \rangle}{(E_d - E_p)}$$

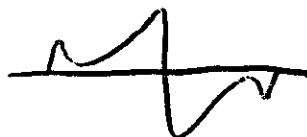
eg $\downarrow g_1 \quad \downarrow g_2 \quad \downarrow g_3 \rightarrow H.$

random orientations (powder)



$H \rightarrow$

Derivative



Local disorder



$H \rightarrow$

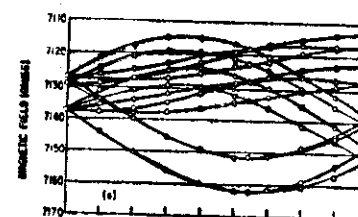
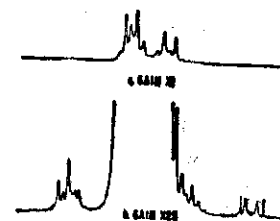


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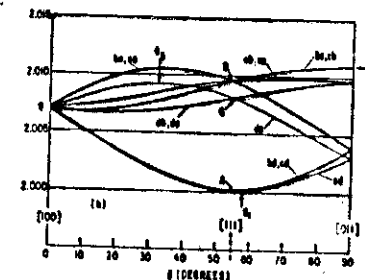
ESR xtal Si

Vacancy-Phosphorus center

ESR absorption

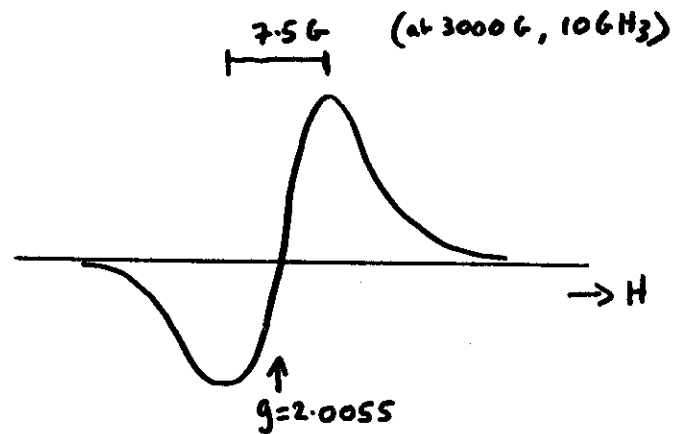


rotating sample (011) plane



model

ESR in a-Silicon

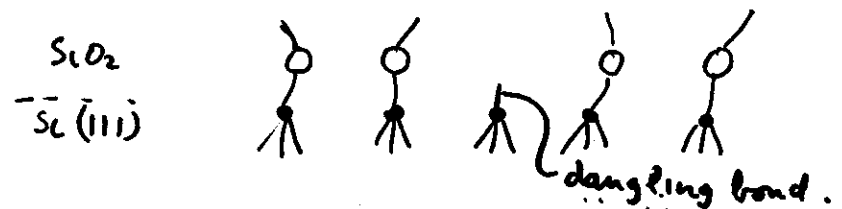


observed

- in Evaporated or Sputtered a-Si
 $N_s \sim 10^{19}/\text{cm}^3$
- in Glow Discharge or Sputtered a-Si:H
 $N_s \sim 10^{15} - 10^{18} \text{ cm}^{-3}$
- in bombarded crystalline Si
- in poly crystalline Si.

Inhomogeneous line is. distribution of g-values

xtal Si / SiO₂ interface



Observation

ESR $g_{\uparrow} = 2.0012$
 $g_{\downarrow} = 2.0082$

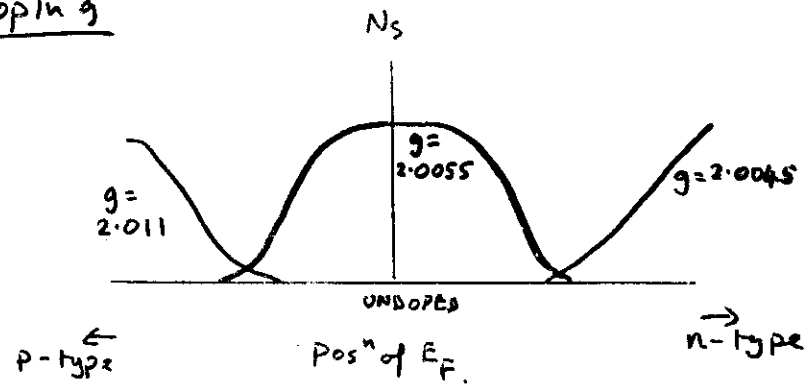
$N_s \sim 10^{12}/\text{cm}^2$ surface spins

identified as dangling bonds

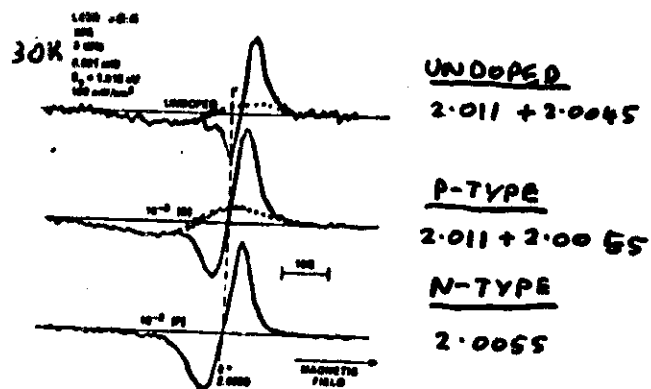
Take powder pattern + disorder broadening
 $\Rightarrow g \approx 2.0055$

Implies that ESR in a-Si is
also dangling bond.

Doping

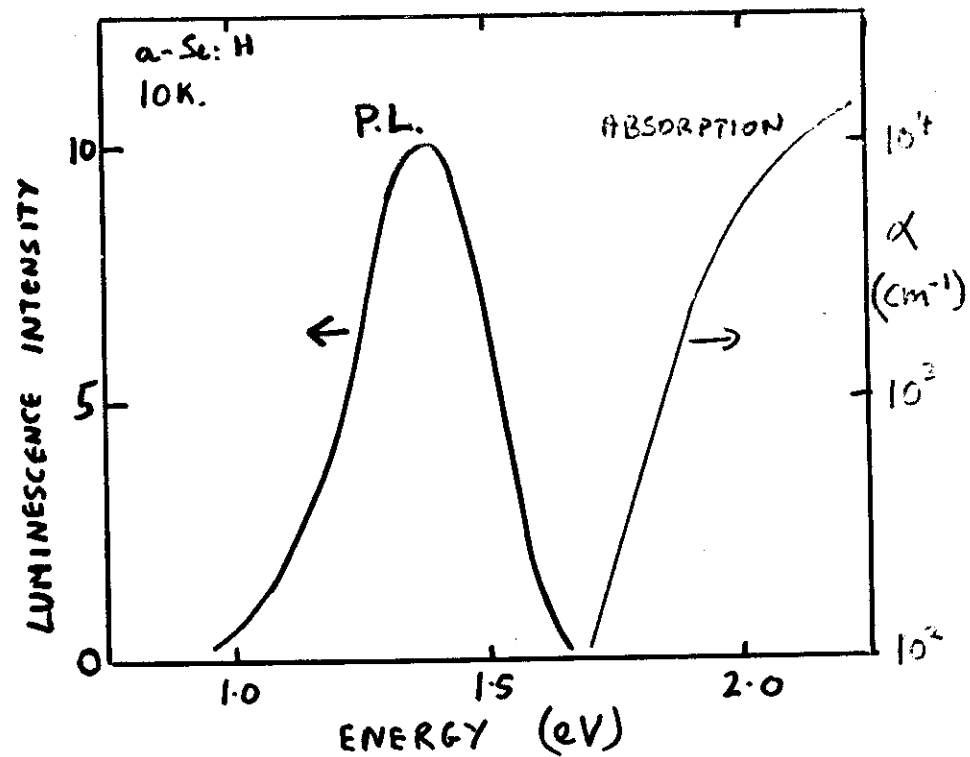


LIGHT INDUCED ESR



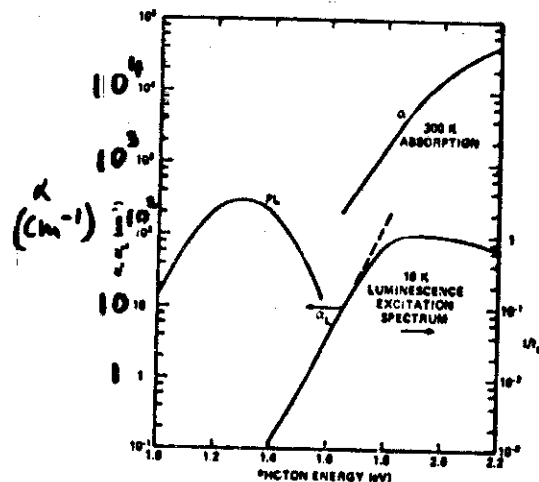
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LUMINESCENCE IN a-Se:H



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Phonon Coupling?



Detailed balance

$$\tau^{-1} = \frac{8\pi n^2}{\lambda^2} \left(\frac{g_1}{g_2} \right) N^{-1} \int \lambda d\nu$$

Recombination rate = $y_L G = N_{occ} \tau^{-1}$

$$\leq N \tau^{-1} = \frac{8\pi n^2}{\lambda^2} \left(\frac{g_1}{g_2} \right) \int \lambda d\nu$$

therefore gives lower bound on $\int \lambda d\nu$

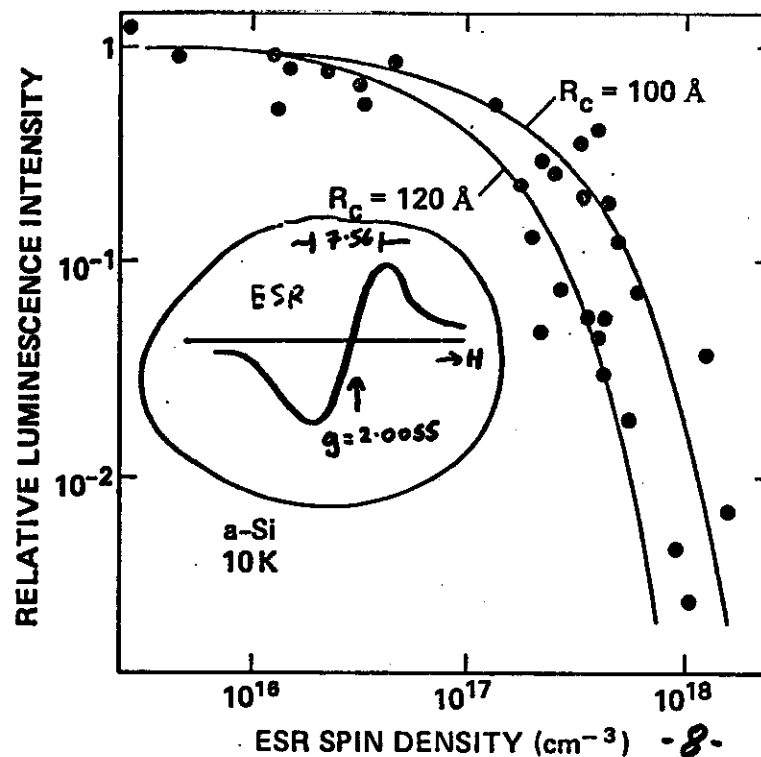
but too large by $\sim 10^4$

$\therefore$ phonon coupling

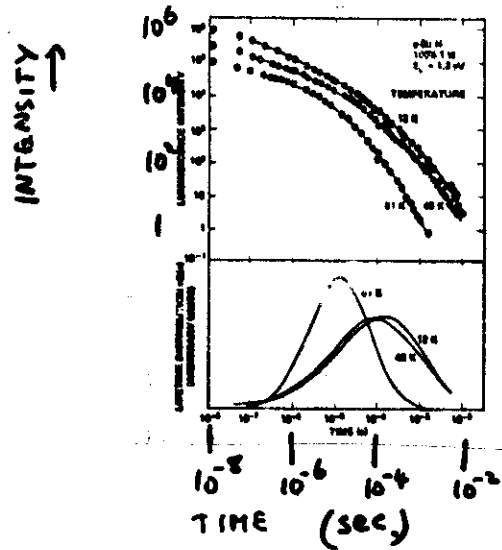
Estimate Zero Phonon Energy $\sim 1.6 - 1.7 \text{ eV}$

Stokes Shift $\sim 0.4 \text{ eV}$

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Luminescence Decay



Decay times extend from 10⁻⁷ sec to 10⁻² sec

mostly 10⁻⁴ - 10⁻³ sec

⇒ very weak overlap

⇒ tunnelling between localized states

$$\tau = \tau_0 \exp(2R/R_0)$$

↑
10⁻⁸

$$R/R_0 \sim 5$$

Calculation of Non-Radiative Transition Rate to Defects

- 1) Define critical Transfer Radius R_c as distance for which Non-Rad Rate = Rad. Rate.

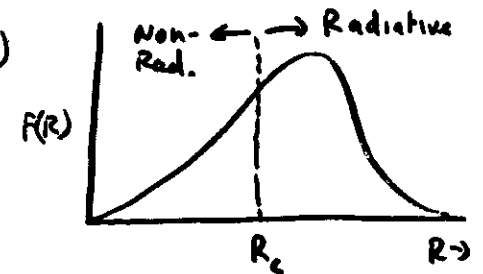
$$\omega_0 \exp(-2R_c/R_0) = \tau_R^{-1}$$

$$\text{or } R_c = \frac{R_0}{2} \ln(\omega_0 \tau_R) \quad \begin{matrix} 10^{-4} \text{ sec} \\ 10^{12} \text{ sec}^{-1} \end{matrix}$$

$$R_c \approx 10 R_0$$

- 2) For a random distribution of defects nearest-neighbour distance given by

$$F(R) = 4\pi R^2 N \exp(-\frac{4}{3}\pi R^3 N)$$

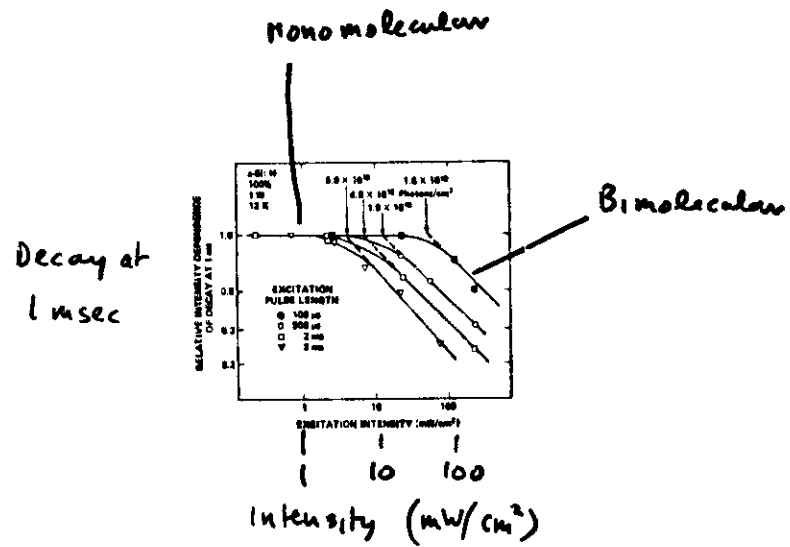


So Luminescence efficiency given by

$$\eta_L = \int_{R_c}^{\infty} F(R) dR = \exp(-\frac{4}{3}\pi R_c^3 N)$$

$$\text{Data } \Rightarrow R_0 \sim 10 \text{ \AA}$$

Recombination Kinetics



Interpreted as transition from
Geminate to non-geminate recombination

Transition occurs at a pair density
 $\sim 10^{18} \text{ cm}^{-3}$

$\Rightarrow$ Pair radius $\sim 50 \text{ \AA}$